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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Alexander T. SCHWARM

Serial No. 10/765,921

Filed: January 29, 2004

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Group Art Unit: 2125

Examiner:

For: **SYSTEM, METHOD, AND MEDIUM FOR MONITORING PERFORMANCE OF AN
ADVANCED PROCESS CONTROL SYSTEM**

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Copies of any cited U.S. Patents and U.S. Patent Publications are not being submitted in accordance with 37 CFR 1.98(a)(2)(i).

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

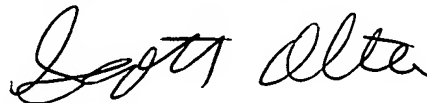
In accordance with 37 C.F.R. § 1.97(g) and (h), the filing of this IDS should not be construed as a representation that a search had been made or that information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56 (b), or that any cited document listed or attached is (or constitutes) prior art. Unless otherwise indicated, the date of

publication indicated for an item is taken from the face of the item, and Applicant reserves the right to prove that the date of publication is in fact different.

No fee is believed to be required; however, the Commissioner is authorized to charge any deficiency in any fees pursuant to 37 CFR § 1.17 associated with this communication and to credit any excess payment to Deposit Account No. 08-0219.

Respectfully submitted,

WILMER CUTLER PICKERING HALE AND DORR LLP




Scott M. Alter
Registration No. 32,879

1455 Pennsylvania Avenue, NW
Washington, DC 20004


TEL 202.942.8428 SMA/lrm

FAX 202.942.8484

Date: 10/8/04

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)				ATTY. DOCKET NO. 007733 USA/ FPS/MMCS/APC		SERIAL NO. 10/765,921	
				APPLICANT Alexander T. SCHWARM			
				FILING DATE January 29, 2004		GROUP 2125	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <p style="text-align: center;">(PTO-1449)</p> 	<p>ATTY. DOCKET NO. 007733 USA/ FPS/MMCS/APC</p>	<p>SERIAL NO. 10/765,921</p>
	<p>APPLICANT Alexander T. SCHWARM</p>	
	<p>FILING DATE January 29, 2004</p>	<p>GROUP 2125</p>
<p style="text-align: center;">OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</p>		
	<p>IslamRaja, M. M., C. Chang, J. P. McVittie, M. A. Cappelli, and K. C. Saraswat. May/June 1993. "Two Precursor Model for Low-Pressure Chemical Vapor Deposition of Silicon Dioxide from Tetraethylorthosilicate." <i>J. Vac. Sci. Technol. B</i>, Vol. 11, No. 3, pp. 720-726.</p>	
	<p>Kim, Eui Jung and William N. Gill. July 1994. "Analytical Model for Chemical Vapor Deposition of SiO₂ Films Using Tetraethoxysilane and Ozone" (Abstract). <i>Journal of Crystal Growth</i>, Vol. 140, Issues 3-4, pp. 315-326.</p>	
	<p>Guo, R.S, A. Chen, C.L. Tseng, I.K. Fong, A. Yang, C.L. Lee, C.H. Wu, S. Lin, S.J. Huang, Y.C. Lee, S.G. Chang, and M.Y. Lee. June 16-17, 1998. "A Real-Time Equipment Monitoring and Fault Detection System." <i>Semiconductor Manufacturing Technology Workshop</i>, pp. 111-121.</p>	
	<p>Lantz, Mikkel. 1999. "Equipment and APC Integration at AMD with Workstream." <i>IEEE</i>, pp. 325-327.</p>	
	<p>July 15, 2004. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.</p>	
	<p>August 2, 2004. Office Action for U.S. Serial No. 10/174,377, filed June 18, 2002.</p>	
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	<p>September 9, 2004. Written Opinion for PCT Serial No. PCT/US02/21942.</p>	
	<p>September 16, 2004. International Preliminary Examination Report for PCT Serial No. PCT/US02/24859.</p>	
EXAMINER	DATE CONSIDERED	

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